Kavli Nanolab Delft
Enabling nanodevice fabrication

Recipe for S1805 resist

Application

Substrate preparation: it is preferable to process the silicon substrate by evaporation of HMDS at 150˚C for 45 sec, using the Delta RC80.

Tone	Positive
Reference	Shipley
Spin coat	0.5 µm @4000 RPM
Pre bake	1 min @115˚C on hotplate
Sensitivity	45 mJ/cm²
Exposure time	Approx. 4.5 sec @ 10 mW/cm²
Development	30 sec in MF321
Stopping of development	30 sec in H_2O

Results

Spin curve